

*FI contd.*  
*DI contd.*

any one of an opening part or a depressed part formed in an insulating film on a substrate;  
a barrier layer covering said opening part or said depressed part, said barrier layer being made of a first material;  
a metal growth promoting layer on said barrier layer, said metal growth promoting layer being made of a second material that is different from said first material of said barrier layer; and  
an electroconductive layer embedded in said opening part or said depressed part via said barrier layer and said metal growth promoting layer.

*huk*  
*F0*

3. (Amended Three Times) An embedded electroconductive layer comprising:

*DZ*

any one of an opening part or a depressed part formed in an insulating film on a substrate;  
a barrier layer covering said opening part or said depressed part;  
a metal growth promoting layer on said barrier layer, said metal growth promoting layer being made of a material different from that of said barrier layer; and  
an electroconductive layer embedded in said opening part or said depressed part via said barrier layer and said metal growth promoting layer;

*D2*  
*cont'd.*  
*F2.*

wherein said metal growth promoting layer is a TiN layer containing oxygen at a lower concentration than said barrier layer.

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37. (New Claim) The embedded electroconductive layer according to claim 1, wherein said metal growth promoting layer has a thickness of at least approximately 10nm.

38. (New Claim) The embedded electroconductive layer according to claim 37, wherein said metal growth promoting layer has a thickness of approximately 20nm.

39. (New Claim) The embedded electroconductive layer according to claim 1, wherein said barrier layer has a thickness of at least approximately 10nm.

*D3*  
*Sub*  
*61*

40. (New Claim) The embedded electroconductive layer according to claim 3, wherein said first material is  $WN_x$ , where  $x$  is a variable such that  $0 \leq x \leq 1$ .

41. (New Claim) The embedded electroconductive layer according to claim 3, wherein said first material is  $TaN_x$ , where  $x$  is a variable such that  $0 \leq x \leq 1$ .